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PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE  
(Case No. 98,162-B)

In re Application of:

DeGendt, et al.

Serial No.: 09/207,546

Filed: December 8, 1998

For: METHOD FOR REMOVING ORGANIC  
CONTAMINANTS FROM A  
A SEMICONDUCTOR SURFACE

Group Art Unit: 1746

Examiner: Ahmed

Commissioner for Patents  
Washington, D.C. 20231



AMENDMENT

Dear Sir:

In response to the outstanding Office Action mailed August 30, 2000, please enter the following remarks and amendments in the above-referenced patent application.

IN THE CLAIMS

Please cancel claims 1-26, 34 and 36-39 without prejudice. Please amend claim 29 as follows:

29. (Amended) A method for removing contaminants from a silicon substrate comprising the steps:

holding said substrate in a tank;

filling said tank with a fluid mixture comprising water, [and] ozone and an additive acting

as a scavenger to thereby achieve an oxide growth on said substrate;

removing the oxide; and

drying the silicon wafer.

McDONNELL BOEHNEN  
HULBERT & BERGHOFF  
300 South Wacker Drive, Suite 3200  
Chicago, Illinois 60606  
(312) 913-0001